Resource Summary Report

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Kloe UV?KUB 2

RRID:SCR_021141
Type: Tool

Proper Citation

Kloe UV?KUB 2 (RRID:SCR_021141)

Resource Information

URL: https://www.kloe-france.com/en/laser-lithography/photolithography-systems/uv-exposure/uv-kub-2

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Description: Compact exposure masking system is UV-LED masking system equipped with LED based optical head, collimated and homogeneous.One level mask aligner. Its masking function enables to reach resolutions less than 1um. This system is compatible with any of photoresists such as AZ series, Shipley series, SU-8 and K-CL series.

Synonyms: UV?KUB 2 masking system, UV-KUB 2

Resource Type: instrument resource

Keywords: KLOE SA, UV LED masker, exposure masking system, instrument, equipment, USEDit

Funding:

Resource Name: Kloe UV?KUB 2

Resource ID: SCR_021141

Alternate IDs: Model_Number_UV-KUB 2

Record Creation Time: 20220129T080354+0000

Record Last Update: 20250410T071322+0000

Ratings and Alerts

No rating or validation information has been found for Kloe UV?KUB 2.

No alerts have been found for Kloe UV?KUB 2.

Data and Source Information

Source: SciCrunch Registry

Usage and Citation Metrics

We have not found any literature mentions for this resource.